

Reliable Direct Bonded Heterogeneous Integration (DBHi) for AI Hardware

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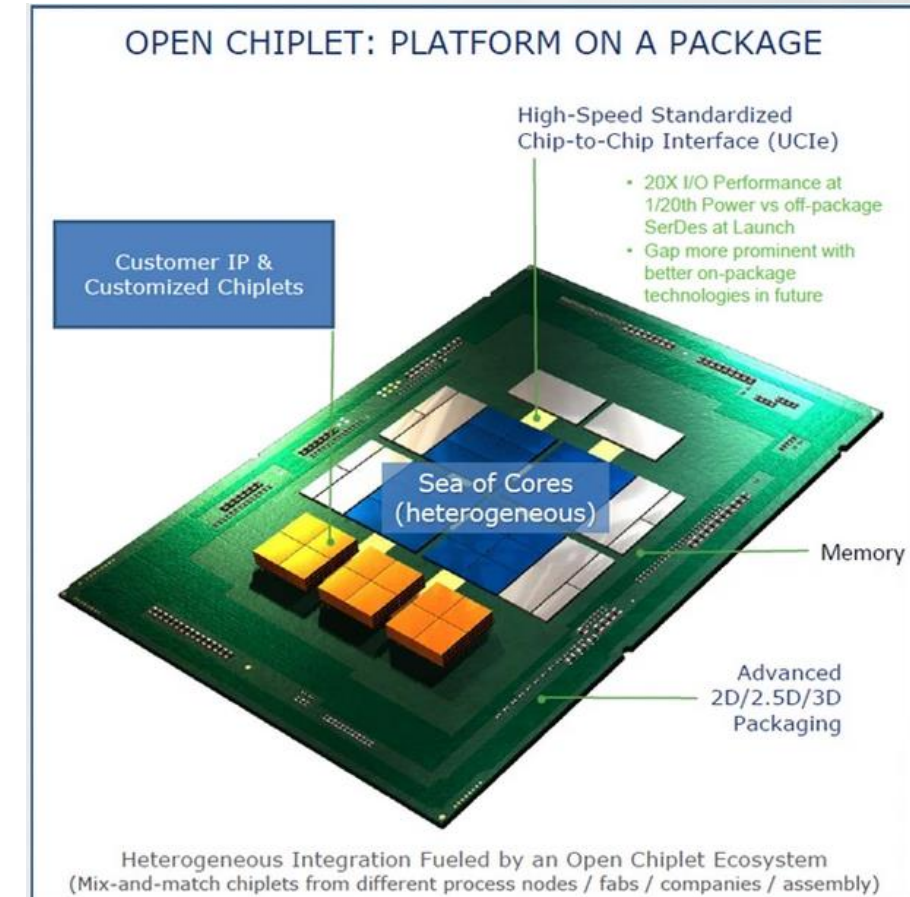
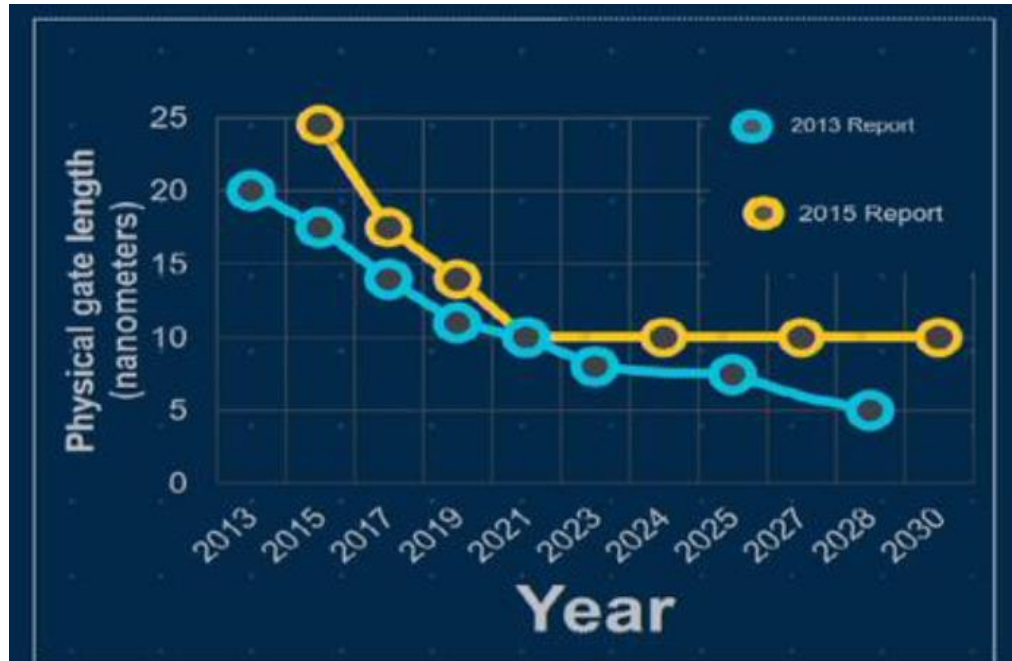
Thomas Wassick
IBM Infrastructure, East Fishkill



Outline

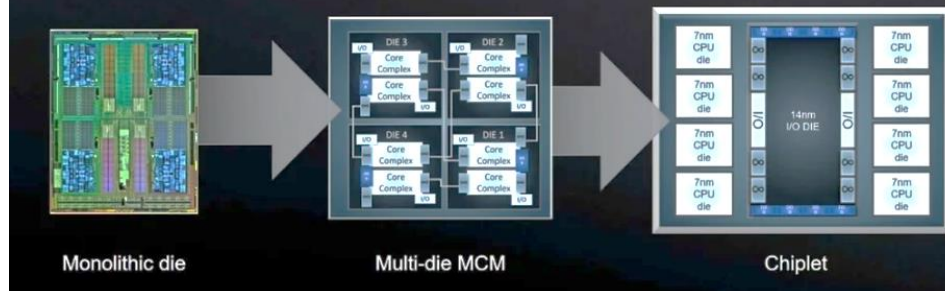
- Introduction to Heterogenous Integration
 - Si bridge technology
- DBHI architecture
 - Bond and Assembly Development
 - 75 μ m pitch
 - Reliability results for Standard and Surface DBHI
 - FA results
 - 30 μ m pitch
 - t(0) results
 - Reliability results for Standard DBHI
- Conclusion

Chiplet Technology (Heterogenous Integration)

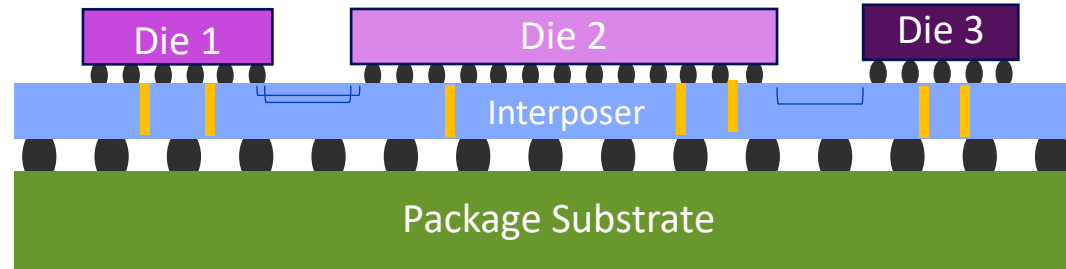


Ref : <https://www.cnx-software.com/2022/03/03/ucie-universal-chiplet-interconnect-express-open-standard-for-chiplets-with-heterogeneous-chips/>

AMD : GPU chiplet technology



Solution for Chiplet Interconnects



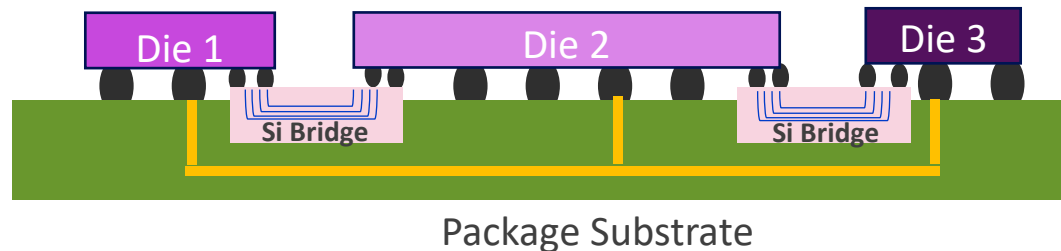
Fanout Interposer

ADVANTAGES

- Lower cost than interposer
- Better Signal Integrity due to signal fanout

DISADVANTAGES

- Requires special processing capabilities
- Limitation with line width/spacing ($>2\mu\text{m}$)



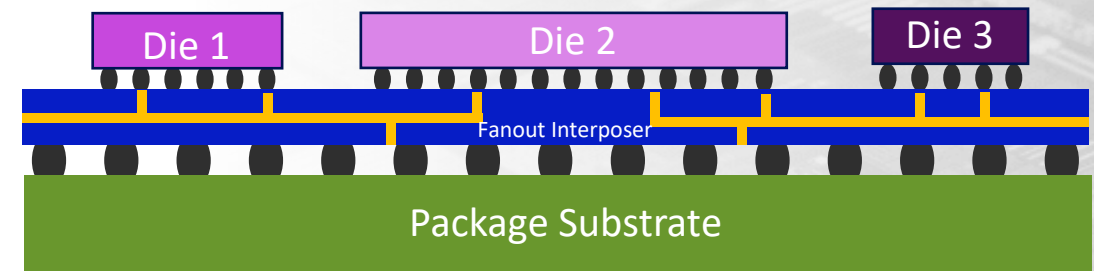
Si Interposer

ADVANTAGES

- Easily adaptable in the Industry
- Finer line width line spacing ($<2\mu\text{m}$)

DISADVANTAGES

- Expensive technology
- lesser signal integrity due to Si



ADVANTAGES OVER SI INTERPOSER :

- Lower cost than Si interposer
- Better Signal Integrity due signal fan out within the package and Si die locally

Si Bridge

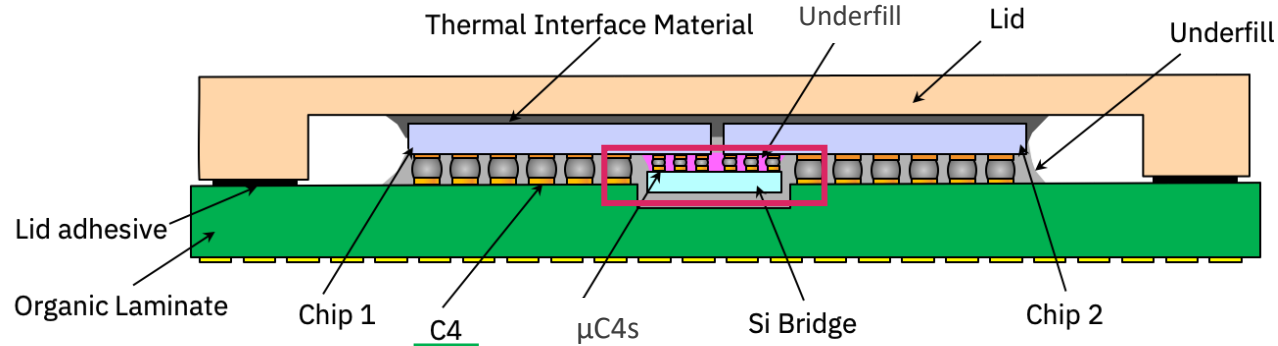
ADVANTAGES OVER FANOUT INTERPOSER :

- Easily adaptable in industry
- Supports finer line width /spacing

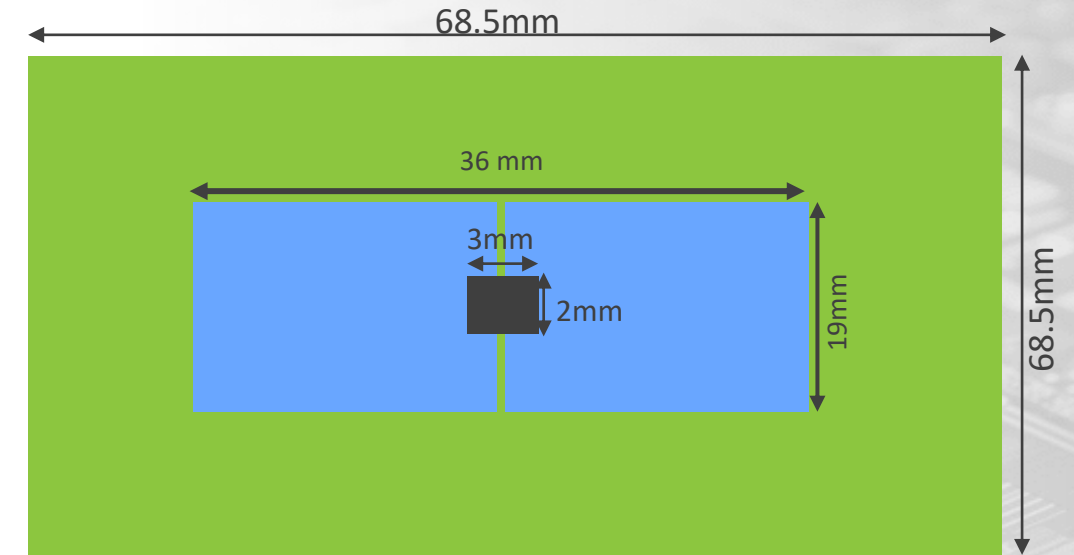
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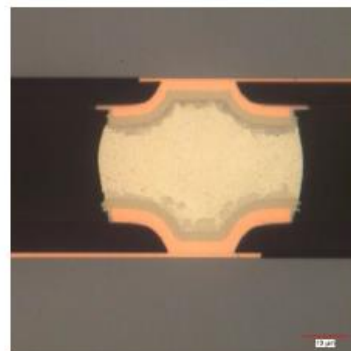
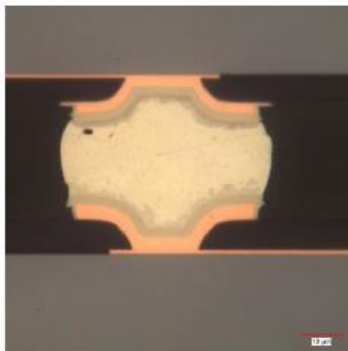
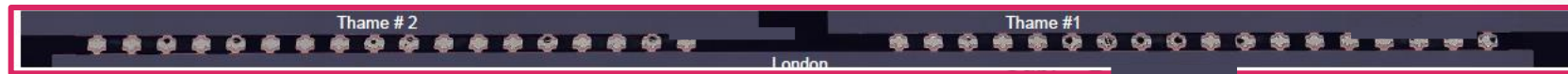
Introduction : DBHI



X-sectional View



Top View * Closer to 1 Reticule size



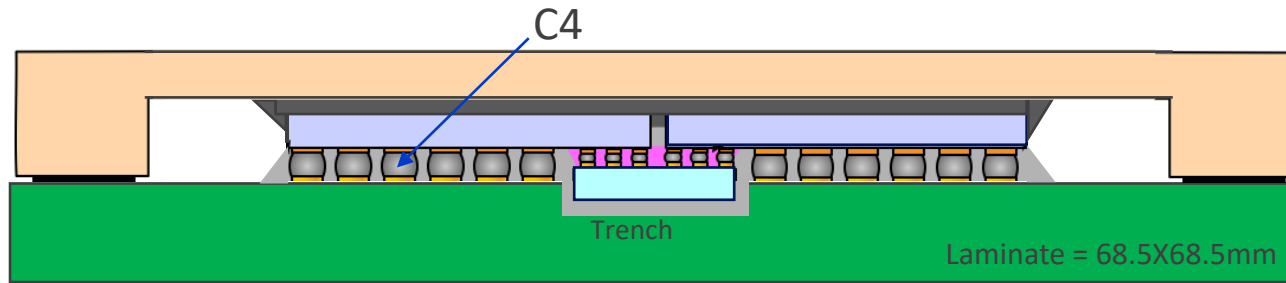
Advantages

- Power Efficiency (0.2pJ/bit)
- Bandwidth Density : <0.5TB/mm/s

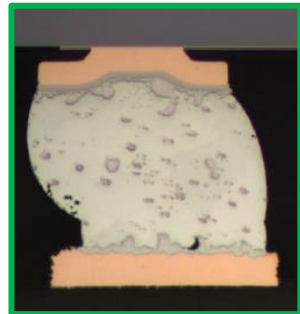
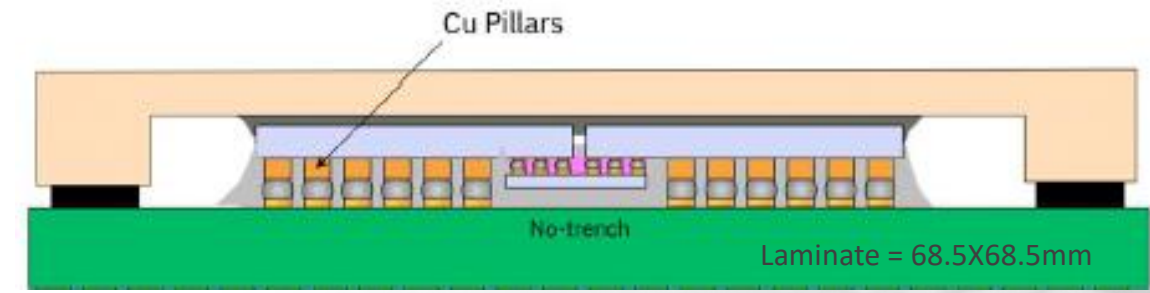
DBHI Architectures

REDEFINING
THE
LIMITS

Standard DBHI



Surface DBHI



C4



Cu pillar

Advantages for Surface DBHI

- Performance : no keep out area below the Si bridge (Flexibility for Signal Routing)
- Process Development : No additional processing for laminate as in case of Standard DBHI

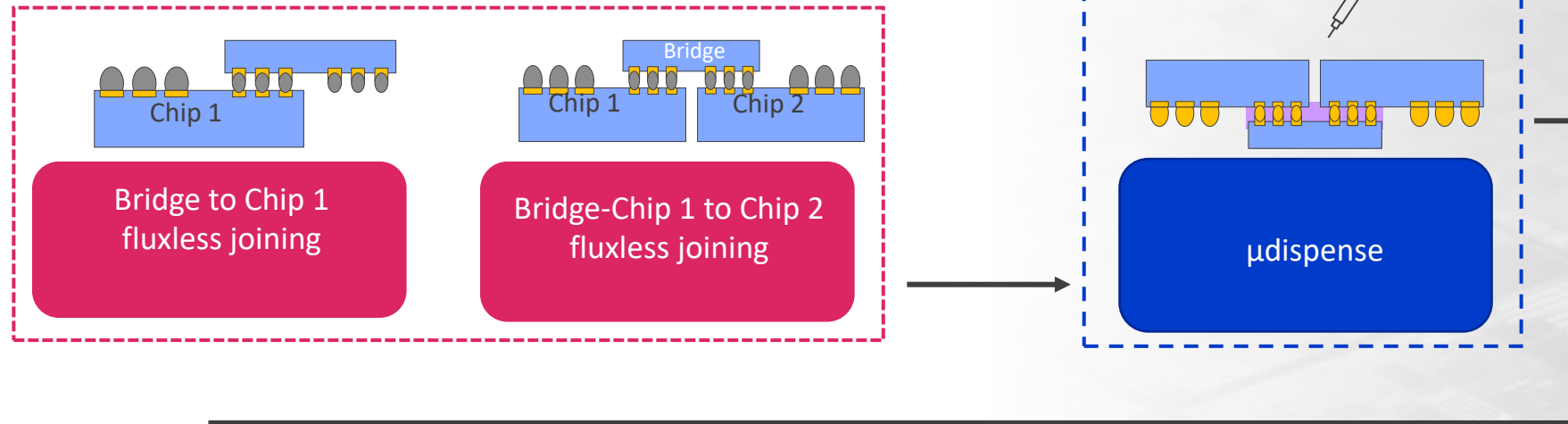
Bond and Assembly Process

REDEFINING
THE
LIMITS

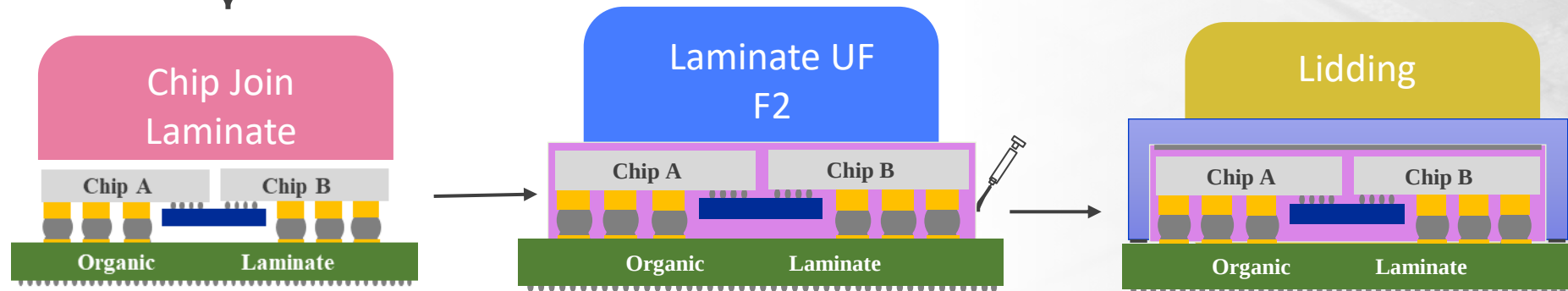
Challenge : Special fixturing to maintain alignment between all the chips in the assembly

Challenge : UF dispense through narrow gap

1. Subassembly



2. Subassembly to Laminate



Challenge : CTE mismatch between laminate and subassembly (Si)

Challenge : Filling UF within the cavity

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Reliability Results : Bridge Nets at 75μm pitch

DTC testing conditions :

-40°C/+125 °C

JEDEC criteria for passing is 850 cycles

Standard-DBHI (75μm pitch)									
Part no.	t(0)	250	500	750	1000	1250	1500	1750	2000
1*	1/29	1/29	1/29	1/29	1/29	1/29	1/29	1/29	1/29
2	0/29	0/29	0/29	0/29	0/29	0/29	0/29	0/29	0/29
3	0/29	0/29	0/29	0/29	0/29	0/29	0/29	0/29	0/29
4	0/29	0/29	0/29	0/29	0/29	0/29	0/29	0/29	0/29
5	0/29	0/29	0/29	0/29	0/29	0/29	0/29	0/29	0/29
Surface - DBHI (75μm pitch)									
1	0/29	0/29	0/29	0/29	0/29	0/29	0/29	0/29	0/29
2	0/29	0/29	0/29	0/29	0/29	0/29	0/29	0/29	0/29
3	0/29	0/29	0/29	0/29	0/29	0/29	0/29	0/29	0/29
4	0/29	0/29	0/29	0/29	0/29	0/29	0/29	0/29	0/29
5	0/29	0/29	0/29	0/29	0/29	0/29	0/29	0/29	0/29

Standard DBHI

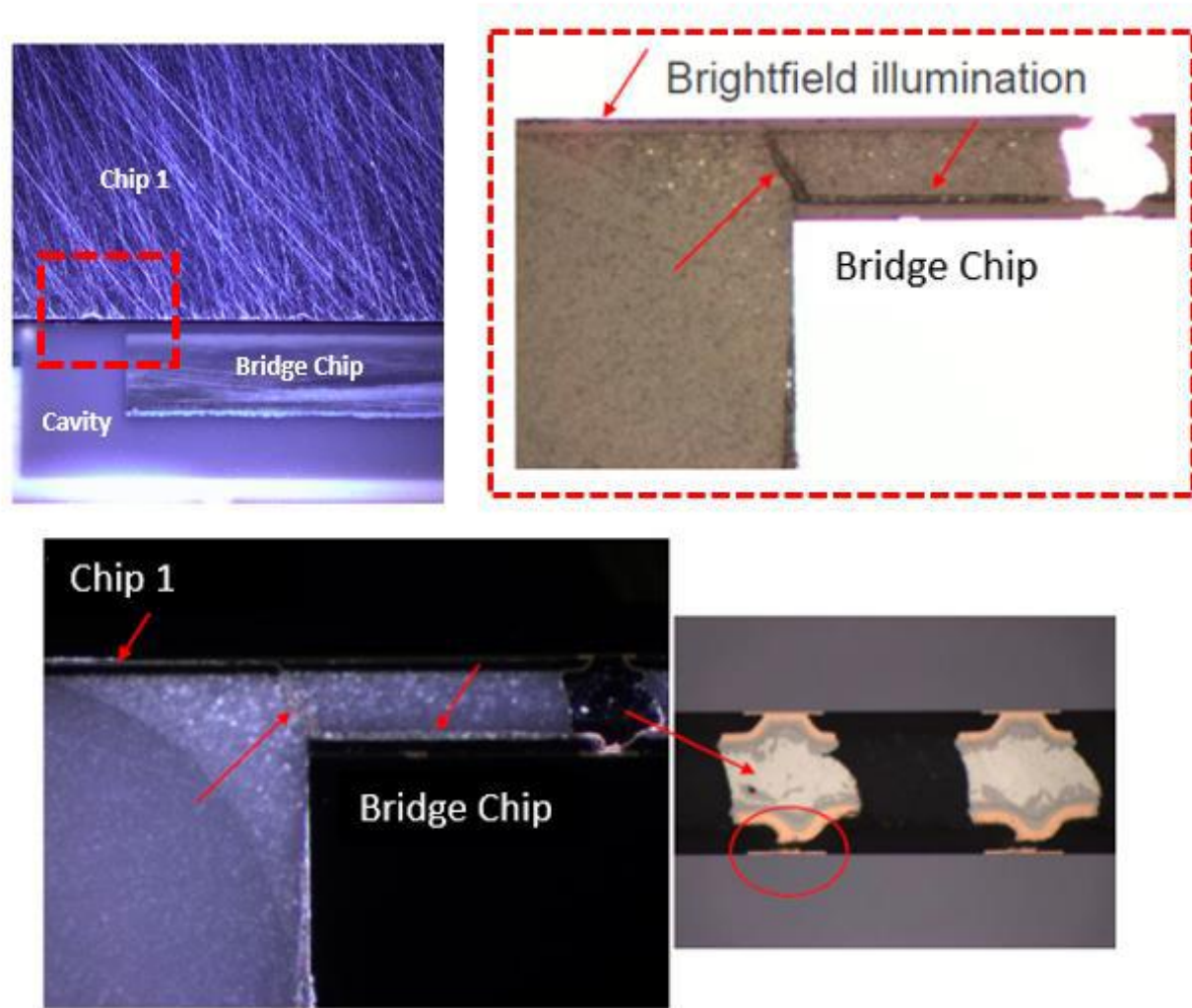
- t(0) yield issue
- 100% pass in extended DTC cycling

Surface DBHI

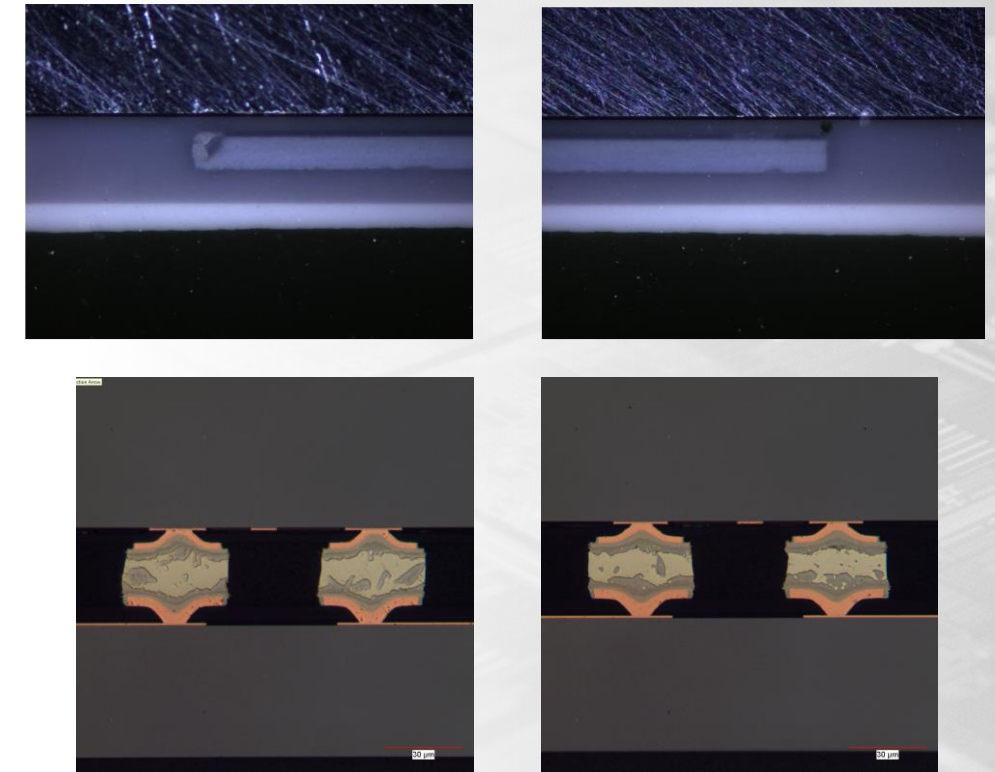
- 100% Yield
- 100% pass in extended DTC cycling

*Tested over 20 parts per condition

Analysis after extended DTC in bridge area

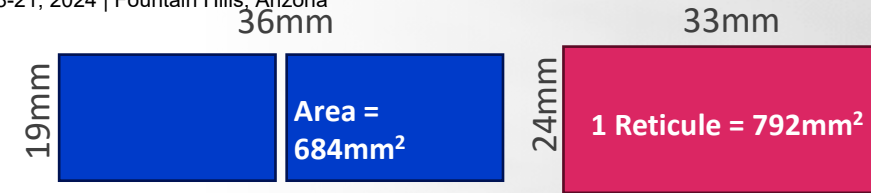


Standard DBHI : Failures are observed in UF that propagates to μ C4 region within Bridge after >2000 DTC cycles



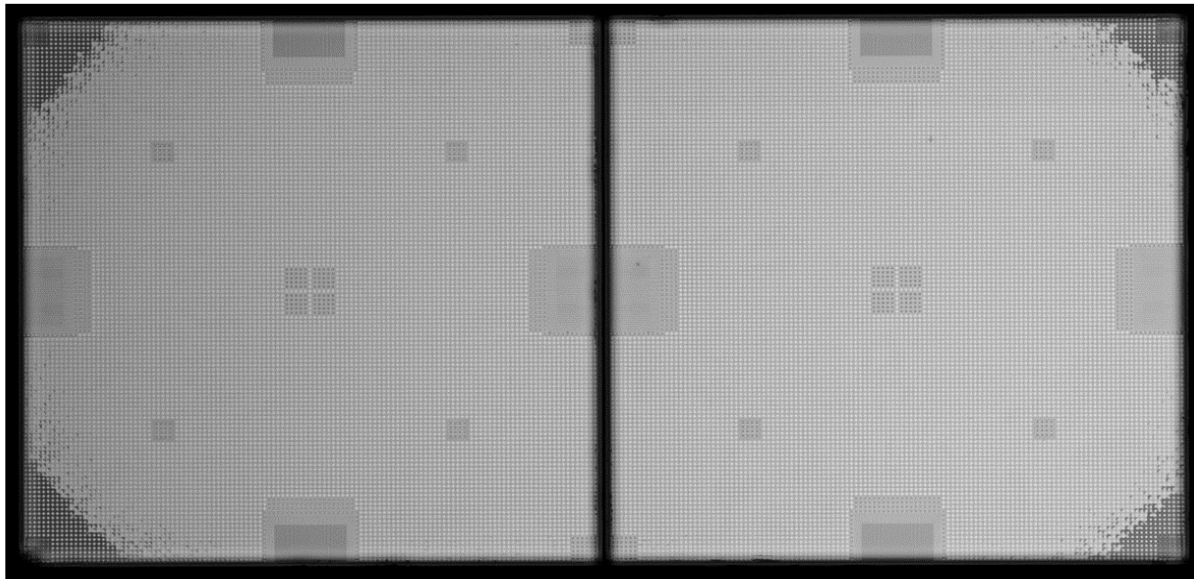
Surface DBHI : Failures are not observed electrical testing and in post analysis also. X-section after >2000 DTC cycles.

Physical Analysis in High DNP area

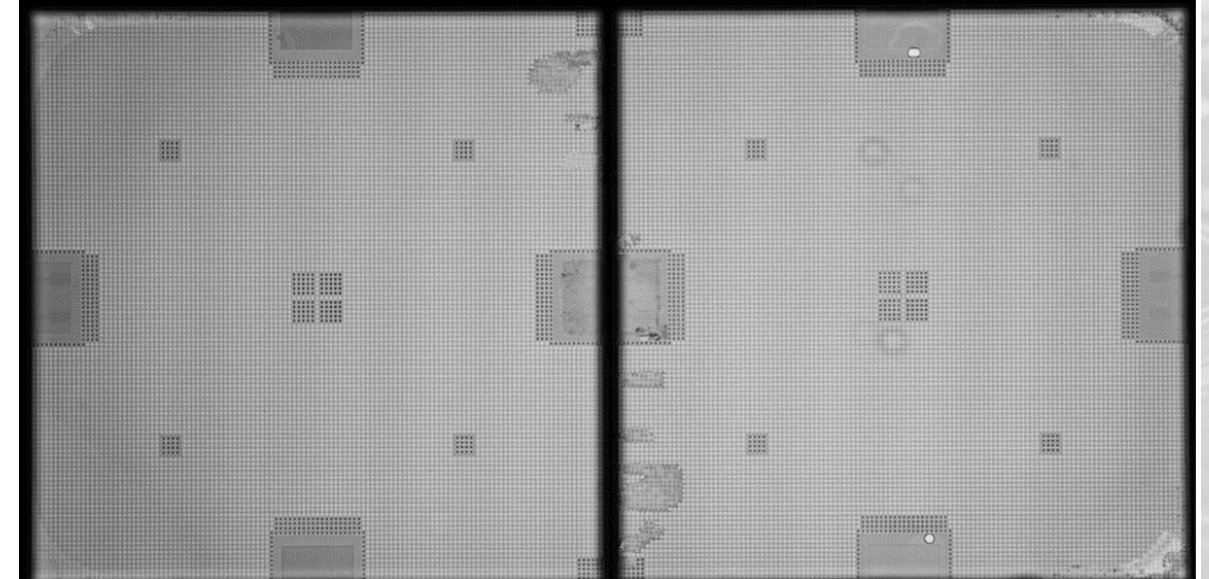


REDEFINING
THE
LIMITS

Scanning Acoustic Analysis after extended cycles of DTC



Standard DBHI

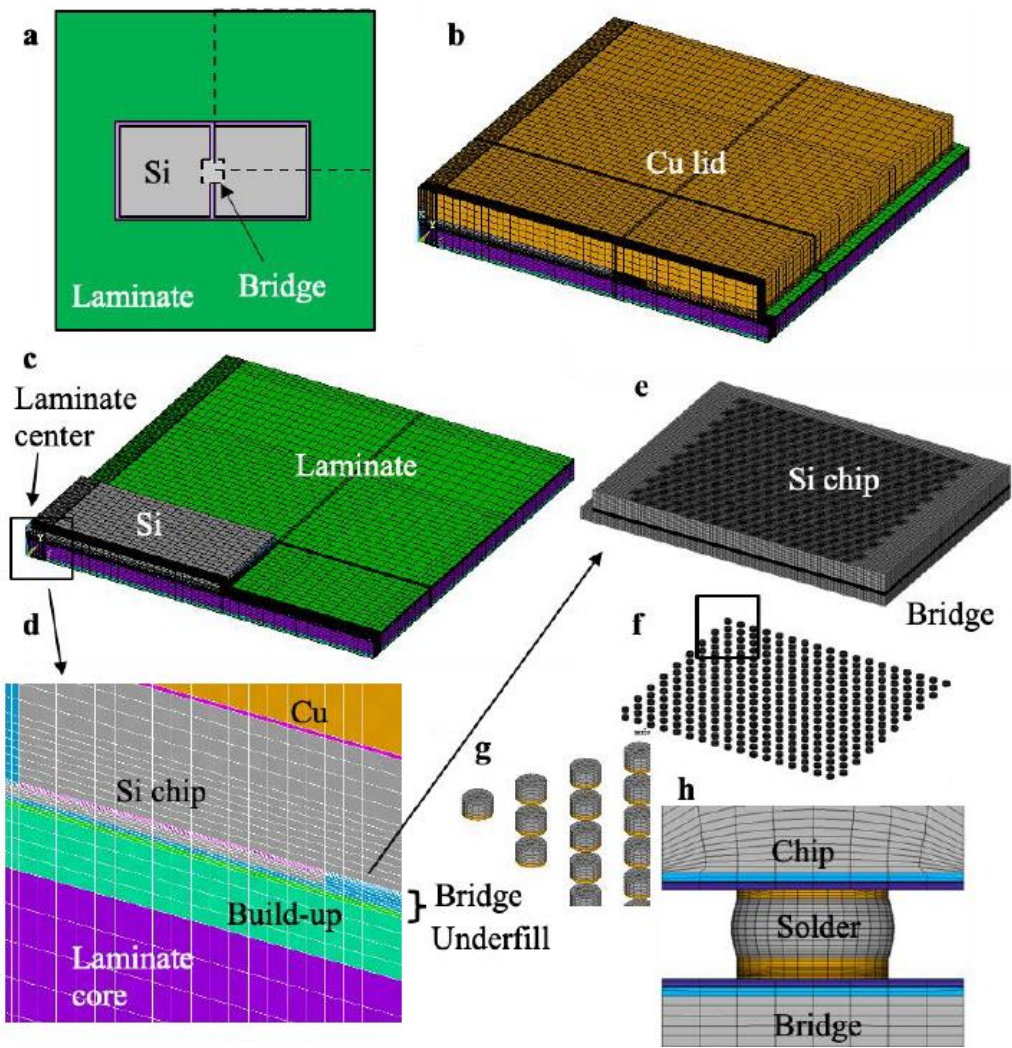


Surface DBHI

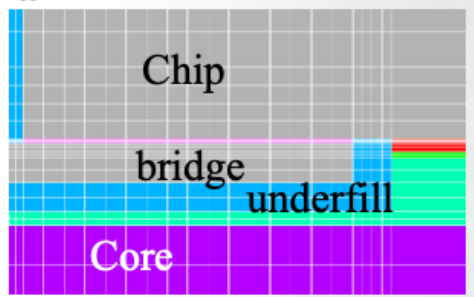
No stiffener is used

Surface DBHI shows lesser impact of stress at chip corners than Standard DBHI

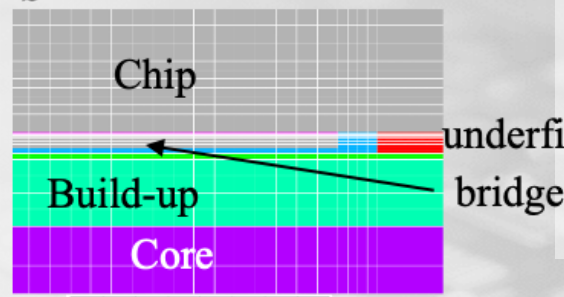
Finite Element Model for DBHi package



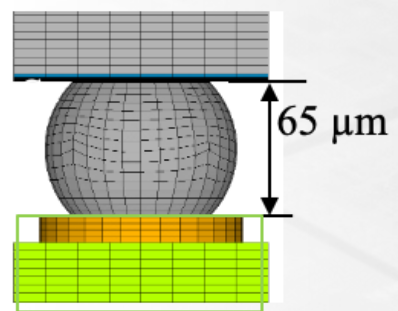
a Standard DBHI



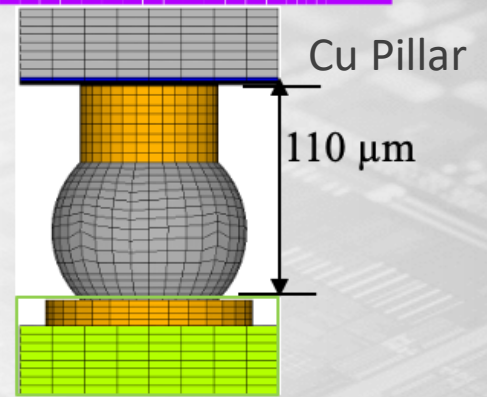
b Surface DBHI



c C4



d



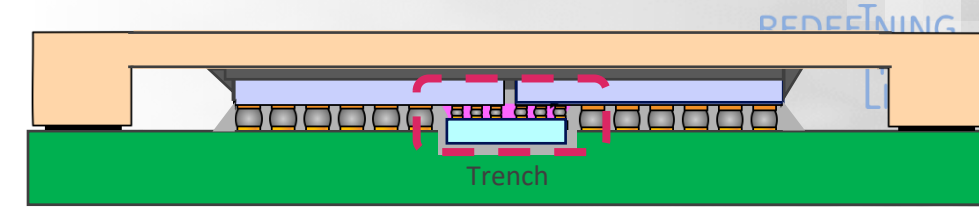
	Standard DBHI	Surface DBHI
UF Stress	X	0.42X
C4 Stress	Y	0.6Y
μC4 Strain	Z	0.8Z

Stresses are lesser in Surface DBHI than Standard DBHi, which explains the Extended DTC cycling results

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Finer pitch at Bridge region – 30μm



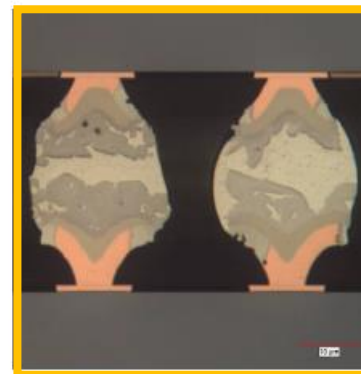
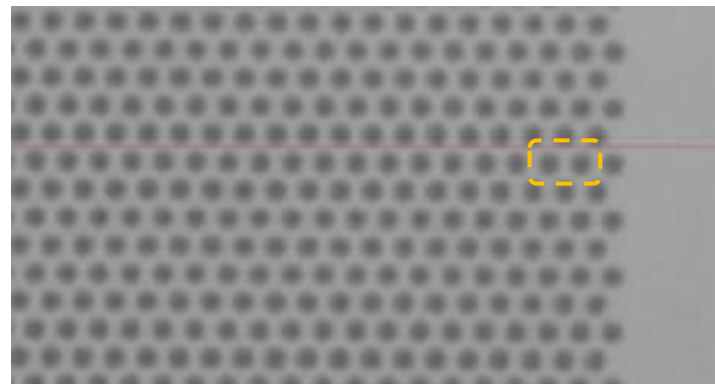
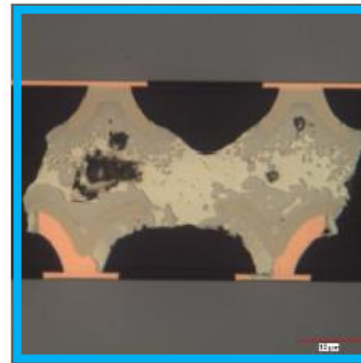
Main challenges for very fine pitch subassembly : Solder height to diameter ratio

Non-optimized solder volume

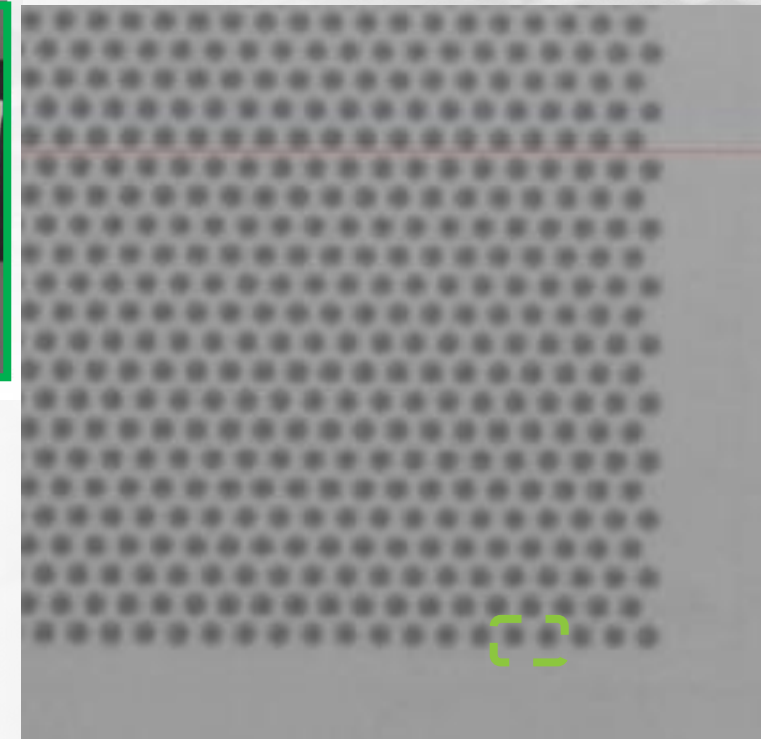
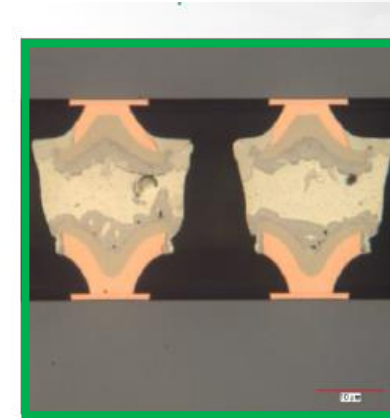
X-RAY of Subassembly



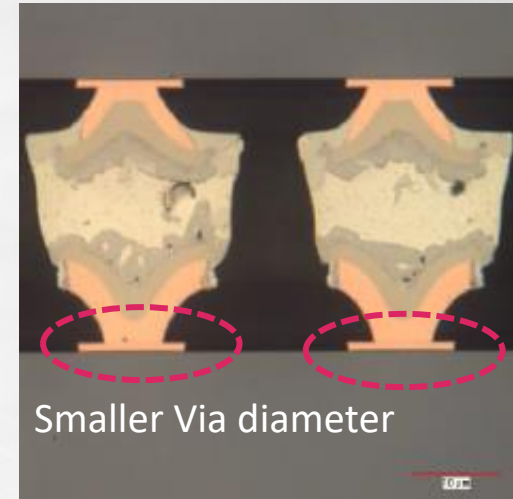
X--section



Optimized solder volume



Results for 30 μ m pitch



Standard DBHI – 30 μ m pitch					
Part no.	t(0)	250 cycles	500 cycles	750 cycles	1000 cycles
1	0/29	1/29	1/29	2/29	2/29
2	0/29	1/29	2/29	2/29	2/29
3	0/29	1/29	4/29	4/29	5/29
4	0/29	0/29	0/29	0/29	0/29
5	0/29	0/29	0/29	0/29	0/29

- **100% Yield of the process**
- **Decent Reliability (DTC) results, but room for improvement**

Reliability can be further improved:

- **Using Surface DBHI architecture (as seen in case of 75 μ m pitch)**
- **By increasing via diameter thus changing BLM structure**

Conclusions

DBHi Architecture with 75 μ m pitch Bridge Region

- Successfully demonstrated Bond and Assembly Process
- Reliability testing demonstrated robust bridge region interconnects for both Surface and Standard DBHI w.r.t. JEDEC criteria
- Surface DBHI architecture is robust as shown by extended DTC cycling (>2000 cycles) and explained by Finite element modelling

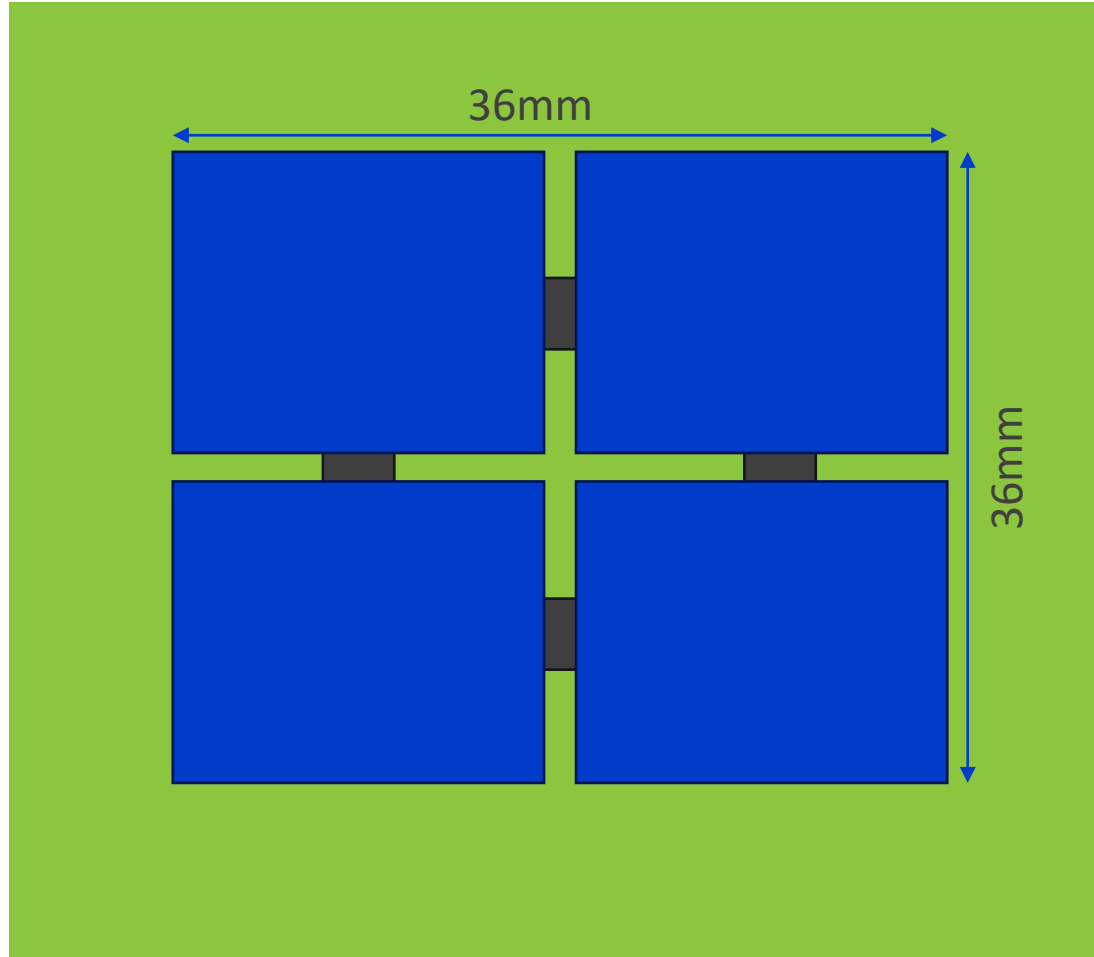
DBHI Architecture with 30 μ m pitch Bridge Region :

- Successfully demonstrated Bond and assembly process with 100% yield
- DTC results (500 cycles) looks promising

Future Work:

- 30 μ m pitch bridge reliability analysis with Surface DBHI architecture and modified BLM
- To extend DBHI architecture to multiple chiplet integration
- For some applications (& in accordance with UCle), bridge needs power supply.
 - Solution : Bridge with TSVs where bridge is connected to the laminate as well

Upcoming Presentation on DBHI



Work on Multiple Chip DBHI will be presented in ECTC 2024 by Akihiro Horibe

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IBM Bromont

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Thanks for your Attention

